

SYSTEM AND METHOD FOR MONITORING WAFER FURNACE PRODUCTION EFFICIENCY

ABSTRACT OF THE DISCLOSURE

A system for monitoring wafer throughput per hour in a wafer furnace includes a database, an analysis unit, a comparison unit, and an output unit. The database includes two or more operation histories of the wafer furnace. The analysis unit is coupled to the database. The analysis unit includes logic that retrieves at least one operation history from the database, determines a standard process time and a specification range for the retrieved operation history, and receives a current process time for the current process. The comparison unit, which is coupled to the analysis unit, includes logic that compares the standard process time and the specification range to the current process time. The output unit, which is coupled to the comparison unit, includes logic that outputs a comparison result. A method for monitoring wafer throughput per hour in a wafer furnace also is described.